CITY OF ELKHART, INDIANA
INDUSTRIAL WASTE QUESTIONNAIRE

SECTION A. GENERAL INFORMATION (Type or Print, Please)

1. Company Name E C M PHOTO TOOLING, INC.

2. Mailing Address 2405 Oakland Ave., Elkhart, IN 46517

3. Address of Premises Same

4. Name and Title of Signing Official J. Michael Seniff

5. Wastewater discharges to:

   City sewer system X

   Private septic system _____

6. If your facility discharges to the City sewer system, check the types of discharges:

   X Sanitary _____ Wash water X Rinse water

   X Cooling water _____ Process water _____ Scrubber water

   _____ Other _____

   Note: If your facility discharges only to a private septic system and not to the City sewer system, or if only sanitary sewage is discharged to the City sewer system, it is only necessary to fill out Section A of this questionnaire. Otherwise, complete entire questionnaire.

7. Contact Official

   Name Dennis Gruntman

   Title Vice President

   Address 2405 Oakland Ave., Elkhart, IN 46517

   Phone Number 295-0189

The information contained in this questionnaire is familiar to me and to the best of my knowledge and belief, such information is true, complete, and accurate.

4/16/84 J. Michael Seniff
Date Signature of Official

SECTION B. PRODUCT OR SERVICE INFORMATION

1. Brief description of manufacturing or service activity on premises:

Phototooling, Chemical Machining and Plating

2. Principal Raw Materials Used:

Copper, Ferric Chloride, Tin, Sulfuric Acid

3. Catalysts, Intermediates:

N/A

4. Principal Product or Service (use Standard Industrial Classification Manual if appropriate): 3679, 3471

5. Appended to this questionnaire is a list of Standard Industrial Classification (SIC) codes for industries currently or potentially subject to USEPA preteatment regulations. List SIC codes for each of your processes that are subject to USEPA pretreatment regulations.

3479 (Chemical Machining), 3471 (Electroplating)

SECTION C. PLANT OPERATIONAL CHARACTERISTICS

1. Type of Discharge: _____ Batch _____ Continuous __X__ Both

For batch discharges, list types, average number of batches/24 hrs. and volume (gallons) per batch. 8 oz./gal. cleaner tank - 50 gal. once per 4 month; 2 oz./gal. Caustic Soda - 100 gal. once per two weeks.

2. Is there a scheduled shutdown? No

When? _____

3. Is production seasonal? No

If yes, explain indicating months(s) of peak production.

_____

4. Average number of employees per shift: 16 1st; ___ 2nd; ___ 3rd

5. Shift start times: 7:30 am 1st; _____ 2nd; _____ 3rd

6. Shifts normally worked each day of the week:

	Sun	Mon	Tue	Wed	Thu	Fri	Sat
1st		X	X	X	X	X	X
2nd							
3rd							

7. Describe any wastewater treatment equipment or processes in use:

None

SECTION D. WATER CONSUMPTION AND LOSS

1. Raw Water Sources:

Source	Quantity
City	2795 gallons per day
	_____ gallons per day
	_____ gallons per day
	_____ gallons per day

2. Water treatment processes in use:

_____ Chemical coagulation, including use of alum, ferric chloride, polymers, etc.

_____ Lime softening

_____ Resin (ion exchange) water softening

_____ Filtration

_____ Chemical (chlorine or ozone) disinfection

_____ Others _____

_____

3. List Water Consumption in Plant:

Cooling Water	395 gallons per day	None contact
Boiler Feed	_____ gallons per day	
Process Water	2240 gallons per day	
Sanitary System*	160 gallons per day	
Contained in Product	_____ gallons per day	
Other ( )	_____ gallons per day	

*Sanitary flow can be estimated at 10 gpd per employee.

4. List average volume of discharge or water loss to:

City Wastewater Sewer	2765	gallons per day
Septic Tank Discharge		gallons per day
Surface Discharge		gallons perday
Waste Hauler		gallons per day
Evaporation	30	gallons per day
Contained in Product		gallons per day

5. Is Discharge to Sewer: _____ Intermittent X Steady

6. List average water usage for SIC Processes itemized in Section B-5 above:

Regulated SIC No.	Brief Process Description	Average Water Consumption(GPD)
3471	Tin Plating	450
3479	Chemical Machining	2185

SECTION E. SEWER CONNECTION AND DISCHARGE INFORMATION

1. List plant sewer outlets and flow: (assign sequential reference number to each sewer starting with No. 1).

Reference No.	Descriptive Location of Sewer Connection or Discharge Point	Avg. Flow (gpd)
1, 2 & 3	Chemical Milling	2185
6	Plating	450
7	Photo lab.	50

2. Attach a scaled drawing or dimensioned sketch of the industrial complex showing location of sewer referenced in E-1 above and location of the SIC process described in Section D-5. Show location of monitoring manhole, if any, and other possible sampling points for sewers and SIC process effluents. Indicate how City industrial monitoring staff can gain access to the sampling points. For reference and field orientation buildings, streets, alleys, and other pertinent physical structures should be included.

   See attached Drawing

3. Is plant required to prepare a Spill Prevention Control and Countermeasure (SPCC) Plan per 40 CFR 112 or a RCRA Contingency Plan?
   ___?___ If report has been prepared, attach copy. Copy attached.
   _____ If report is required, but has not yet been prepared, indicate date when it will be submitted. _____

SECTION F. PRIORITY POLLUTANT INFORMATION

1. Please indicate by placing an "X" in the appropriate box by each listed chemical whether it is Suspected to be Absent, Known to be Absent, Suspected to be Present, or Known to be Present in your manufacturing or service activity or generated as a byproduct. Some compounds are known by other names. Please refer to Appendix A for those compounds which have an asterisk(*).

ITEM NO.	CHEMICAL COMPOUND	SUSPECTED ABSENT	KNOWN ABSENT	SUSPECTED PRESENT	KNOWN PRESENT	ITEM NO.	CHEMICAL COMPOUND	SUSPECTED ABSENT	KNOWN ABSENT	SUSPECTED PRESENT	KNOWN PRESENT
1.	ammonia		X			47.	chlorobenzene		X		
2.	asbestos (fibrous)		X			48.	chloroethane*		X		
3.	cyanide (total)		X			49.	2-chloroethylvinyl ether		X		
						50.	chloroform*		X		
4.	antimony (total)		X			51.	chloromethane*		X		
5.	arsenic (total)		X			52.	2-chloronaphthalene		X		
6.	beryllium (total)					53.	2-chlorophenol*		X		
7.	cadmium (total)		X			54.	4-chlorophenylphenyl ether		X		
8.	chromium (total)		X			55.	chrysene*		X		
9.	copper (total)				X	56.	4,4'-DDD*		X		
10.	lead (total)		X			57.	4,4'-DDE*		X		
11.	mercury (total)		X			58.	4,4'-DDT*		X		
12.	nickel (total)				X	59.	dibenzo(a,h)anthracene*		X		
13.	selenium (total)		X			60.	dibromochloromethane*		X		
14.	silver (total)		X			61.	1,2-dichlorobenzene*		X		
15.	thallium (total)		X			62.	1,3-dichlorobenzene*		X		
16.	zinc (total)		X			63.	1,4-dichlorobenzene*		X		
						64.	3,3'-dichlorobenzidine		X		
17.	acenaphthene		X			65.	dichlorodifluoromethane*		X		
18.	acenaphthylene		X			66.	1,1-dichloroethane*		X		
19.	acrolein		X			67.	1,2-dichloroethane*		X		
20.	acrylonitrile		X			68.	1,1-dichloroethene*		X		
21.	aldrin		X			69.	trans-1,2-dichloroethene*		X		
22.	anthracene		X			70.	2,4-dichlorophenol		X		
23.	benzene		X			71.	1,2-dichloropropane*		X		
24.	benzidine		X			72.	(cis & trans)1,3-dichloropropene*		X		
25.	benzo(a)anthracene*		X								
26.	benzo(a)pyrene*		X			73.	dieldrin		X		
27.	benzo(b)fluoranthene		X			74.	diethyl phthalate*		X		
28.	benzo(g,h,i)perylene*		X			75.	2,4-dimethylphenol*		X		
29.	benzo(k)fluoranthene*		X			76.	dimethyl phthalate		X		
30.	a-BHC (alpha)		X			77.	di-n-butyl phthalate		X		
31.	b-BHC (beta)		X			78.	di-n-octyl phthalate*		X		
32.	d-BHC (delta)		X			79.	4,6-dinitro-2-methylphenol*		X		
33.	g-BHC* (gamma)		X			80.	2,4-dinitrophenol		X		
34.	bis(2-chloroethyl)ether*		X			81.	2,4-dinitrotoluene		X		
35.	bis(2-chloroethoxy)methane*		X			82.	2,6-dinitrotoluene*		X		
36.	bis(2-chloroisopropyl)ether*		X			83.	1,2-diphenylhydrazine*		X		
37.	bis(chloromethyl)ether*		X			84.	endosulfan I*		X		
38.	bis(2-ethylhexyl)phthalate*		X			85.	endosulfan II*		X		
39.	bromodichloromethane*		X			86.	endosulfan sulfate		X		
40.	bromoform*		X			87.	endrin		X		
41.	bromomethane*		X			88.	endrin aldehyde		X		
42.	4-bromophenylphenyl ether		X			89.	ethylbenzene		X		
43.	butylbenzyl phthalate		X			90.	fluoranthene		X		
44.	carbon tetrachloride*		X			91.	fluorene*		X		
45.	chlordane		X			92.	heptachlor		X		
46.	4-chloro-3-methylphenol*		X			93.	heptachlor epoxide		X		

SECTION F. PRIORITY POLLUTANT INFORMATION (CON'T)

ITEM NO.	CHEMICAL COMPOUND	SUSPECTED ABSENT	KNOWN ABSENT	SUSPECTED PRESENT	KNOWN PRESENT	ITEM NO.	CHEMICAL COMPOUND	SUSPECTED ABSENT	KNOWN ABSENT	SUSPECTED PRESENT	KNOWN PRESENT
94.	hexachlorobenzene*		X			112.	PCB-1248*		X		
95.	hexachlorobutadiene		X			113.	PCB-1254*		X		
96.	hexachlorocyclopenta-		X			114.	PCB-1260*		X		
	diene*		X			115.	pentachlorophenol		X		
97.	hexachloroethane*		X			116.	phenanthrene		X		
98.	indeno(1,2,3-cd)pyrene*		X			117.	phenol		X		
99.	isophorone*		X			118.	pyrene		X		
100.	methylene chloride*		X			119.	2,3,7,8-tetrachlorodi-		X		
101.	naphthalene		X				benzo-p-dioxin*		X		
102.	nitrobenzene		X			120.	1122-tetrachloroethane*		X		
103.	2-nitrophenol*		X			121.	tetrachloroethene*		X		
104.	4-nitrophenol*		X			122.	toluene*		X		
105.	n-nitrosodimethylamine*		X			123.	toxaphene		X		
106.	n-nitrosodipropylamine*		X			124.	1,2,4-trichlorobenzene		X		
107.	n-nitrosodiphenylamine*		X			125.	1,1,1-trichloroethane*		X		
108.	PCB-1016*		X			126.	1,1,2-trichloroethane*		X		
109.	PCB-1221*		X			127.	trichloroethene*		X		
110.	PCB-1232*		X			128.	trichlorofluoromethane*		X		
111.	PCB-1242*		X			129.	2,4,6-trichlorophenol		X		
						130.	vinyl chloride*		X		

2. For chemical compounds in F-2 above which are indicated to be "Known Present," please list and provide the following data for each: (attach additional sheets if needed).

ITEM NO.	CHEMICAL COMPOUND	ANNUAL USAGE(LBS)	ESTIMATED LOSS TO SEWER LBS./YR.	ITEM NO.	CHEMICAL COMPOUND	ANNUAL USAGE(LBS)	ESTIMATED LOSS TO SEWER LBS./YR.
9	Copper	8000	?				
72	Nickel	50	?				

3. List any other chemicals known or anticipated to be present in the discharge.

None

4. Describe, what if any, laboratory analyses have been conducted on process waste streams in the plant, including which streams were sampled, what parameters were measured, and frequency and type of samples. (The baseline report referred to in G2 below can be referenced in answering this question.)

None to Date - Composite sample will be taken at manhole and analyzed.

SECTION G. PRETREATMENT

1. Is this plant subject to an existing Pretreatment Standard?

?

2. Is this plant required to submit a baseline report per 40 CFR 403.12? ? If a baseline report has been prepared, attach a copy to this questionnaire. Copy attached. _____ If a baseline report is required, but has not yet been prepared, indicate date that it will be submitted. _____

3. If subject to Federal Pretreatment Standards, are the standards being met on a consistent basis? (The baseline report can be referred to in answering this question.)

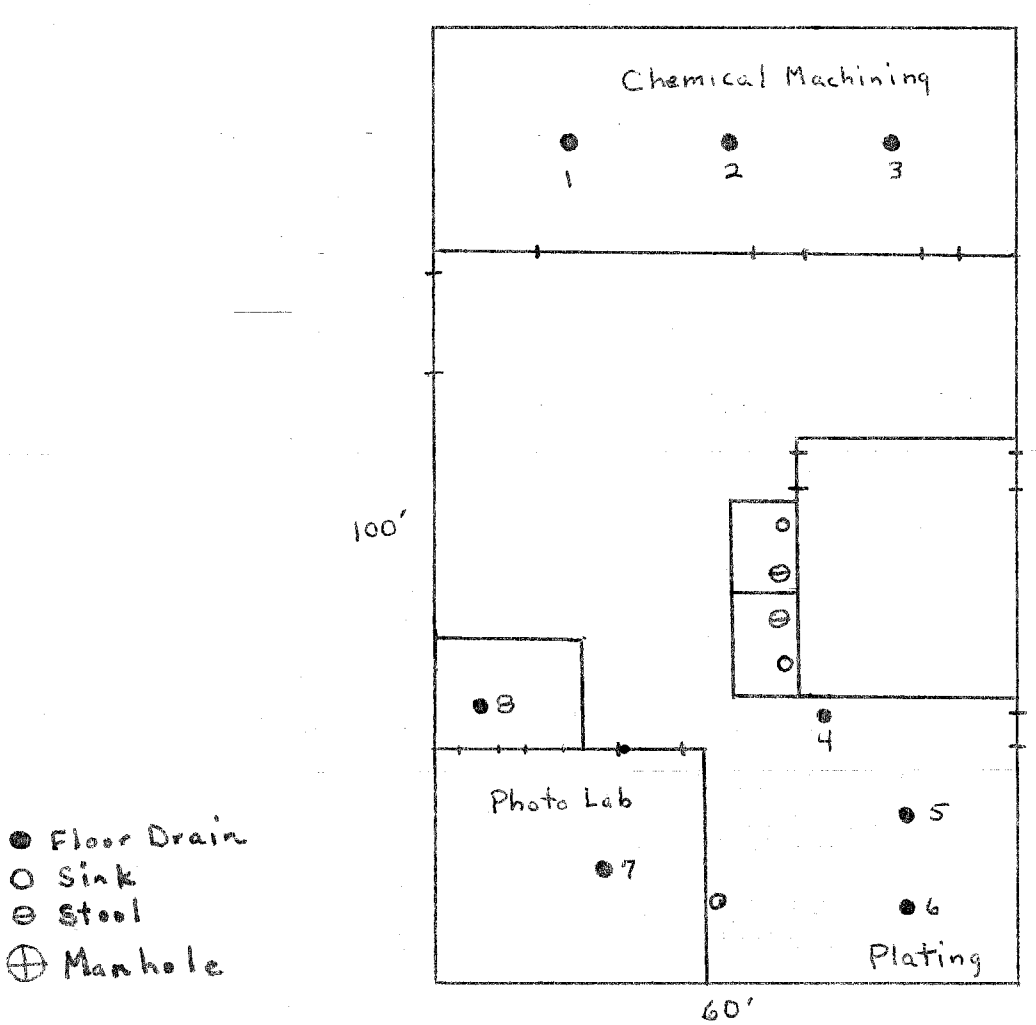
?

4. Are additional pretreatment facilities and/or operation and maintenance required to meet Pretreatment Standards? If additional pretreatment and/or operation and maintenance are required, list the schedule by which they will be provided. (The baseline report can be referred to in answering this question.)

?

5. Describe residuals (sludges, precipitates, etc.) that are produced or result at your facility and the methods employed to dispose of the residuals. List names of waste haulers, if applicable.

Spent Ferric Chloride - Triple "S" Etchant (waste Hauler)



ECM Photo Tooling
2405 Oakland Ave.

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